

Notice of References Cited	Application/Control No. 10/758,817		Applicant(s)/Patent Under Reexamination MARKS, RICHARD L.	
	Examiner KENT WANG		Art Unit 2622	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-7,106,366	09-2006	Parker et al.	348/222.1
*	B	US-7,061,507	06-2006	Tuomi et al.	345/611
*	C	US-5,914,723	06-1999	Gajewska, Hania	345/597
*	D	US-6,134,346	10-2000	Berman et al.	382/163
*	E	US-2003/0012277	01-2003	Azuma et al.	375/240.08
*	F	US-5,557,684	09-1996	Wang et al.	382/107
*	G	US-5,706,364	01-1998	Kopec et al.	382/159
*	H	US-7,161,634	01-2007	Long, Wai Khaun	348/624
*	I	US-7,283,679	10-2007	Okada et al.	382/260
*	J	US-6,556,704	04-2003	Chen, Shoupu	382/154
	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Gvili et al., Depth Keying, SPIE Vol 5006(2003), SPIE-IS&T, pp 564-574
	V	
	W	
	X	

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
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